

REMARKS

35 USC §§102 AND 103

Claims 1, 3, 11-13, 26-28 and 31 are rejected under 35 USC §102(e) as being anticipated by Putzer (US Patent Publication 2004/0122197).

Claims 1, 4-15 and 27-28 are rejected under 35 USC §103(a) as being unpatentable over Kennedy et al (US 6506497) in view of Putzer (US Patent Publication 2004/0122197).

Claims 1 and 37 are rejected under 35 USC §103(a) as being unpatentable over Kennedy et al (US 6506497) in view of Putzer (US Patent Publication 2004/0122197), and further in view of Dammel et al. (US Patent Publication 2004/0166434).

The Applicant respectfully disagrees.

Claim 1 recites:

"An absorbing composition comprising at least one inorganic-based compound, at least one organic-based absorbing compound, and at least one material modification agent, wherein the at least one material modification agent comprises at least one adhesion promoter, at least one crosslinking agent, at least one porogen, at least one catalyst, at least one capping agent, at least one pH tuning agent or a combination thereof, wherein the at least one adhesion promoter comprises APTEOS triflate, APTEOS methanesulfonate, APTEOS nitrate, APTEOS nfbs, ammonium triflate, ammonium nfbs, ammonium methanesulfonate, ammonium nitrate, TMAH triflate, TMAH nfbs, TMAH methanesulfonate, TMAA, TMAN, TMAH nitrate or a combination thereof, wherein the at least one adhesion promoter does not initiate significant crosslinking activity in the composition, and wherein the absorbing compound strongly absorbs light over at least an approximately 0.5 nm wide wavelength range at wavelengths less than 375 nm." (emphasis added)

After discussing this case in full with the inventors, it is clear that the Putzer publication is quite different from the current application, and therefore, claim 1 is herein amended to clarify the difference. The Putzer publication states:

"This invention relates to a polyorganosiloxane composition, a method of combining the components and a method of vulcanizing said polyorganosiloxane composition, the vulcanized composition obtainable thereby, composite materials containing a substrate and said vulcanized composition as well as the use of the polyorganosiloxane composition."
(emphasis added)

In addition, paragraphs [0039]-[0046] explicitly disclose that the adhesion promoters are utilized by inducing crosslinking between the components of the composition, wherein the adhesion promoters are crosslinking agents.

Claim 1 is amended herein to include the provision "wherein the at least one adhesion promoter does not initiate significant crosslinking activity in the composition". This provision is supported and described in full on page 20 of the current application:

"In some contemplated embodiments, the at least one adhesion promoter comprises at least one of the following characteristics: a) is thermally stable after heat treatment, such as baking, at temperatures generally used for electronic and semiconductor component manufacture (see Example 2 and **Figures 2-5**); b) has a relatively low catalytic ability, in that the donor does not initiate significant crosslinking activity in the composition to which it is added; c) is relatively neutral, so that the composition retains a low pH; d) is acidic, in order to lower the pH of the composition; e) does not initiate or propagate reactions that increase the molecular weight of species in the

composition to which it is added; f) can surprisingly act as an adhesion promoter by promoting electrostatic and coulombic interactions between layers of materials, as opposed to conventionally understood Van derWaals interactions."

The chemistry in the current application is completely different from the chemistry in the Putzer application, specifically the chemistry of the current application is driven by the bases and the amines are both soluble and minimally reactive (certainly not crosslinking). The Putzer chemistry is the opposite, wherein it specifically discloses significant (and desired) crosslinking and is driven by acid chemistry.

Therefore, Putzer cannot possibly anticipate claim 1 of the current application. In addition, Putzer in combination with Kennedy and/or Dammel does not cure the obvious deficiency of these references in comparison with amended claim 1. Therefore, claim 1 is both novel and patentable over Putzer alone or in combination with Kennedy and/or Dammel.

Claims 1, 3, 7, 11-13, 18, 26, 29-31 and 37 are rejected under 35 USC §103(a) as being unpatentable in view of US Patent 6677392 (Ravichandran et al) in view of Hayashi et al (US Patent Publication No. 2003/0091838). The Applicant respectfully disagrees.

Claim 1 recites:

“An absorbing composition comprising at least one inorganic-based compound, at least one organic-based absorbing compound, and at least one material modification agent, wherein the at least one material modification agent comprises at least one adhesion promoter, at least one crosslinking agent, at least one porogen, at least one catalyst, at least one capping agent, at least one pH tuning agent or a combination thereof, wherein the at least one adhesion promoter comprises APTEOS triflate, APTEOS methanesulfonate, APTEOS nitrate, APTEOS nfbfs, ammonium triflate, ammonium nfbfs, ammonium methanesulfonate, ammonium nitrate, TMAH triflate, TMAH nfbfs, TMAH methanesulfonate, TMAA, TMAN, TMAH nitrate or a combination thereof, wherein the at least one adhesion promoter does not initiate significant crosslinking activity in the composition, and wherein the absorbing compound strongly absorbs light over at least an approximately 0.5 nm wide wavelength range at wavelengths less than 375 nm.”
(emphasis added)

Claim 1 recites an absorbing composition that comprises several components recited above, including that the absorbing compound strongly absorbs light over at least an approximately 0.5 nm wide wavelength range at wavelengths less than 375 nm. According to the Examiner, this provision is patentable in view of the Ravichandran reference, the Hayashi reference and the combination thereof. Therefore, Ravichandran in combination with Hayashi does not render unpatentable claim 1 of the present application. Further, Ravichandran in combination with Hayashi does not render unpatentable claims 3, 7, 11-13, 18, 26, 29-31 and 37 by virtue of their dependency on claim 1.

Honeywell Docket No. H0005567.36146 - 4780
Buchalter Docket No. H9930-0305

REQUEST FOR ALLOWANCE

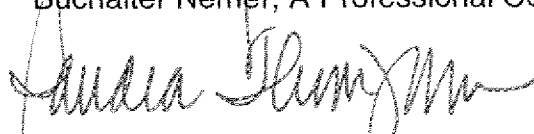
Claims 1, 3, 5-15, 18, 26-31 and 37 are pending in this application. The applicants request allowance of all pending claims.

Respectfully submitted,

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